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## CAPACITIVE RADIOFREQUENCY DISCHARGES AND DUSTY OR COMPLEX PLASMAS FROM FUNDAMENTAL TO APPLICATIONS

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# **OUT LINES**

- Introduction: History and motivations
- Capacitively coupled capacitive discharge (CCCD)
- Particle charging and trapping in the plasma
- Nucleation and growth of dust particles in the gas phase
- Particle detection
- Temperature effects
- Applications
- Conclusions

# From dust in plasmas to dusty plasma science

The first observations of dust in a laboratory plasma were made by Langmuir. He reported these observations on September 18, 1924 at the Centenary of the Franklin Institute in Philadelphia.

Langmuir, Found and Dittmer, Science, vol. 60, No. 1557, p 392 (1924)

"... we have observed some phenomena of remarkable beauty which may prove to be of theoretical interest."



# MORE RECENT WORKS $1924 \rightarrow 1980$

- 1945 : *Kenty and Cooper*: effect of impurities on fluorescent lamps.
- 1966 : *Garscadden and Lee*: constricted discharges.
- 1970 : *Emeleus and Breslin*: effect of dust on positive columns.

# Take off

#### Dusty plasmas in astrophysics



#### In nature

- Comet tails
- Planetary atmospheres (Titan' s atm. cont. N<sub>2</sub>-CH<sub>4</sub>)
- Planetary rings (Saturn' s rings)
- Interstellar clouds





# Take off

**Unexpected dust problems in plasma-surface processing : pioneering works** -e.g. PECVD (a-Si:H): **Spears & al**, **IEEE trans. Plasma Sc. 14, 179, 1986.** -e.g. etching (SiO<sub>2</sub>): **G. Selwyn & al**, **J. Vac. Sci. Techn. A 7, 2758,1989.** 





G.S. Selwyn, Plasma Sources Sci. Tehcnol. 3, 340 (1994).

Images from Gary Selwyn: The original discovery that RF plasmas (etching/deposition) can be appropriat medium for particle growth in the gas phase and particle levitation.

#### CAPACITEVELY COUPLED CAPACITIVE RADIOFREQUENCY DISCHARGES



Frequency range [Hz]	Center frequency [Hz]	Availability
6.765–6.795 MHz	6.780 MHz	Subject to local acceptance
13.553–13.567 MHz	13.560 MHz	
26.957-27.283 MHz	27.120 MHz	
40.66–40.70 MHz	40.68 MHz	
433.05–434.79 MHz	433.92 MHz	only
902–928 MHz	915 MHz	only
2.400-2.500	2.450 GHz	
5.725–5.875 GHz	5.800 GHz	
24–24.25 GHz	24.125 GHz	
61–61.5 GHz	61.25 GHz	Subject to local acceptance
122–123 GHz	122.5 GHz	Subject to local acceptance
244–246 GHz	245 GHz	Subject to local acceptance

« Industrial, Scientific and Medical Frequencies » (ISM)







P. Belenguer et al, Surf Interface Anal., 35, (2003), 604.

The nonlinear relationship between the current and the voltage drop in the sheaths induces harmonics in the current waveform.









# **TYPICAL EXPERIMENTAL CONDITIONS**



Typical parameters for low pressure discharge plasmas Pressure: 10-1000 µbars, gas flow : 1-100 sccm, power : 0.01-1 W/cm<sup>3</sup> Electrical source: RF, DC, microwaves, ionization degree : 10<sup>-5</sup>-10<sup>-3</sup>

#### Low pressure discharge plasmas : typical microscopic characteristics



 $n_i \sim n_e \sim 10^9 - 10^{10} \text{ cm}^{-3}$ 

 $1 \text{ eV} \le \text{T}_{\text{e}} \le 10 \text{ eV}, \text{T}_{\text{i}} \approx 0.03 \text{ eV}$ 

## Low pressure discharge plasmas : typical microscopic characteristics

**Electrons**: achieve gas ionization, dissociation and excitation  $\Rightarrow$  thermal energy of few eV; thermal speed : few 10<sup>6</sup> m.s<sup>-1</sup>

**Ions** : collisional equilibrium with gas  $\Rightarrow$  room temperature, thermal speed = few 100 m.s<sup>-1</sup>

plasma core ~ equipotential limited by space charge sheaths that control charge losses



## Low pressure discharge plasmas : typical microscopic characteristics

- high mobility of electrons: very low potential variation in the plasma core (B = 0)

- **requirement of potential barriers** (sheaths) reducing the electron drift flow to the ion flow level (ambipolar diffusion)

- height of barrier : few kTe/q ( repelling most of the electrons and all negative ions) . All the negatively charged species are trapped in the core of the plasma.

- ions accelerated towards the walls and ion flow velocity at the sheath edge =  $[kT_e / M_i]^{0.5}$  (Bohm velocity).

# DUST PARTICLE CHARGING AND TRAPPING IN LOW PRESSURE PLASMAS

Single particle immersed in the plasma is negatively charged



Here we considered Maxwellian ion energy distribution

 $V_{f}$  and  $V_{p}$  are respectively the dust particle floating and plasma potentials.

The potential drop in the sheath is given by

$$\frac{n_i}{n_e} \sqrt{\frac{T_i m_e}{T_e m_i}} \left(1 - q \frac{V_f - V_p}{k_B T_i}\right) = \exp\left(q \frac{V_f - V_p}{k_B T_e}\right)$$



For an isolated spherical dust particle the acquired maximum charge is given by the following expression

$$Q_d = \frac{4\pi\epsilon_0 k_B T_e}{e} \ln\left(\frac{ni}{n_e} \left(\frac{m_e T_e}{m_i T_i}\right)^{1/2}\right)$$

## PARTICLE CHARGING MECANISMS





Charging by collecting electrons and ions only  $\Rightarrow Q < 0$  Electron emission

- secondary emission due to e<sup>-</sup> impact
- photoemission
- thermionic

#### $\Rightarrow$ Q > 0

Goree, Plasma Sources Sci. Technol. 1994

Secondary emission from small dust grains at high electron energies Chow, V.W. Mendis, D.A. Rosenberg, M. <u>IEEE Transactions on Plasma Science</u>, 179-186, 1994

\*Meyer-Vernet, Astron. Astrophys. 105,98 (1982)

When immersed in a plasma, the dust particle acquire a negative charge and thus is confined in the plasma. It is submitted to a set of forces which are :

- •Gravity
- •Electrical force
- •Ion drag force
- •Neural drag force
- •Thermophoretic force
- •Photophoresis
- •Particle-particle interaction.



•Gravity 
$$F_g = \frac{4}{3}\pi r_d^3 \rho g$$

•Electrical Force : 
$$F_e = Q_d E_0 \left[ 1 + \frac{(r_d / \lambda_L)^2}{3(1 + r_d / \lambda_L)} \right]$$

•Ion Drag force  $\vec{F}_i = \vec{F}_i^o + \vec{F}_i^c = \pi b_c^2 n_i v_s m_i \vec{u}_i + 4\pi b_{\pi/2}^2 H n_i v_s m_i \vec{u}_i$ 

•with 
$$b_c^2 = r_d^2 \left( 1 - 2q \frac{V_f - V_p}{m_i v_i^2} \right)$$
 and  $H = \frac{1}{2} \ln \left( \frac{\lambda_e^2 + b_{\pi/2}^2}{b_c^2 + b_{\pi/2}^2} \right)$ 

•Thermophoretic force

$$\vec{F}_{th} = -\frac{32}{15} \frac{r_d^2}{v_{th,n}} \left[ 1 + \frac{5\pi}{32} (1 - \alpha_T) \right] \kappa_T \vec{\nabla} T_{gas}$$

#### Momentum is imparted to the dust particle



Ion orbit is deflected

Ion strikes particle

Comparison of the different forces



# **Dense particle cloud dynamics**

#### Well localized traps



#### Simulation

J.P. Boeuf et al, PSST, 3, (1994) Dalvie et al, PSST, 3, 442-447, (1994)



#### Experiment

Dense particle cloud trapped in plasma : from independent particles to coulomb crystals Strongly coupled systems



1 : When the inter-particle distance is such that their « Debye spheres » overlapp : repelling forces appear

2 : If the kinetic energy is significantly lower than the interaction energy the particles cannot move freely

3 : Phase transition (liquid to crystal) predicted theoretically before experimental evidence

4 : Crystals defects and wave propagation observed

#### Dense particle cloud trapped in plasma : from independent particles to coulomb crystals



Plasma ON : particle velocity RMS value = 0.0220 m/s

kinetic energy :  $kT_d = 0.035 \text{ eV} (T_d = 410 \text{ K})$ 

Plasma OFF : instantaneous gas velocity = 0.215 m/s particle-particle interaction energy : 0. 3 eV

$$\mathbf{rom} \qquad W_{dE} = \frac{1}{4\pi\varepsilon_0} \frac{Z^2 q^2}{D_{p-p}}$$

- dust cloud grown in Ar-SiH<sub>4</sub> plasma filling the whole plasma box - particle diameter : 0.4  $\mu$ m , particle density 10<sup>8</sup> cm<sup>-3</sup>

- particle charge : ~40 electrons
- $\Gamma$  = 10, transition to crystal for > 170 (Ikezi)

-measurement of particle vertical velocity using LDA evidenced a rather incompressible liquid-like behavior *Ikezi H. Phys. Fluids 29, 1764 (1986).* 

## Dense particle cloud trapped in plasma : from independent particles to coulomb crystals

**Evidence of coulombian crystals** 

First publications as early as 1994

Chu & al, J Phys D , <u>27</u>, 296 Melzer & al, Phys Lett. <u>A 320</u>, 301 Hayashi & al, Jpn J. Apl. Phys. <u>33</u>, L 804, Thomas & al , Phys Rev Lett, <u>73</u>, 652





In these experiments  $\Gamma > 1000$ , well above the critical value (170)

#### **Dense particle cloud trapped in plasma : from independent particles to coulomb crystals**





## **INSTABILITIES OF THE GROWN DUST CLOUD (HEARTBEAT)**

Once the dust cloud is completely formed, a dust-free region can appear in the plasma center

#### This region can oscillate spontaneously: Successive contractions and expansions



#### Electrical measurements for different pressures



M. Mikikian, L. Boufendi, Phys. Plasmas 11, 3733 (2004)

## HEARTBEAT INSTABILITY HIGH SPEED IMAGING

#### High speed imaging ~1800 fps

#### **Direct observation of plasma glow**

Dust cloud observed with Laser Light Scattering





M. Mikikian, L. Couëdel, M. Cavarroc, Y. Tessier, L. Boufendi, New J. Phys. 9, 268 (2007)



## HEARTBEAT INSTABILITY HIGH SPEED IMAGING

#### **Direct observation of plasma glow**

#### Evolution of dust cloud during one contraction-



**Evolution of the central column profil during one contraction-expansion sequence** 



M. Mikikian, L. Couëdel, M. Cavarroc, Y. Tessier, L. Boufendi, New J. Phys. 9, 268 (2007)

# **DUST PARTICLE FORMATION**

# **DUST PARTICLE FORMATION**

• The dust particle formation in a plasma can be observed in etching, PECVD and sputtering reactors.

• In all these situations, homogeneous chemical reactions are responsible of this phenomenon.
#### **CHEMICAL REACTIONS IN PECVD REACTORS**









Dark field TEM micrographs evidence elementary structures as 2-3 nm diameter crystallites

Mass spectrometry data give insights on cluster formation process (1 to few 10 Si atoms)



Evidence of a clustering process involving negative ions (trapped)

**Clustering models: take into account neutrals, cations, anions** 

Main route through :

 $[Si_{n}H_{2n+1}]^{-} + S_{i}H_{4}^{*}$ 

 $[S_{in+1+} H_{2n+3}]^{-} + 2H$  $SiH_{3}^{-}$ 

Main results : from EPFL, Lausanne Ch. Hollenstein et al. PSST 3, 278, (1994).

#### Particle nucleation and growth process : characteristic steps in argon - silane discharge,





Growth of carbon particles, from sputtering graphite in an rf discharge

This kind of dust can be also obtained in PECVD plasmas in hydrocarbon chemistries. See J. Winter et al work.

D. Samsonov and J. GoreeParticle growth in a sputtering dischargeJ. Vac. Sci. Technol. A 1999

# DUST PARTICLE NUCLEATION AND GROWTH SIMULATION



Figure 6. Dominant anionic reaction pathways at steady-state ( $T_{gas} = 500 \text{ K}$ ,  $N_i = 3 \times 10^9 \text{ cm}^{-3}$ ); the numbers indicate net reaction rates in units of  $10^{-15} \text{ mol cm}^{-3} \text{ s}^{-1}$ .

#### A. A. Fridman, J. Appl. Phys. 79, 1303, (1996).

- U. V. Bhandarkar et al, J. Phys. D 33, 2731-2746, (2000).
- K. De Bleeker et al, Phys. Rev. E 69, 056409 (2004)

#### **Role of the atomic hydrogen**



$$\begin{split} &\mathrm{SiH}_{3}^{-} + \mathrm{SiH}_{4} = \mathrm{Si}_{2}\mathrm{H}_{5}^{-} + \mathrm{H}_{2} \quad \Delta H = -0.07 \text{ eV}, \\ &\mathrm{Si}_{2}\mathrm{H}_{5}^{-} + \mathrm{SiH}_{4} = \mathrm{Si}_{3}\mathrm{H}_{7}^{-} + \mathrm{H}_{2} \qquad \Delta H = +0.07 \text{ eV}, \\ &\mathrm{Si}_{3}\mathrm{H}_{7}^{-} + \mathrm{SiH}_{4} = \mathrm{Si}_{4}\mathrm{H}_{9}^{-} + \mathrm{H}_{2} \qquad \Delta H = +0.07 \text{ eV}, \\ &\mathrm{Si}_{4}\mathrm{H}_{9}^{+} + \mathrm{SiH}_{4} = \mathrm{Si}_{5}\mathrm{H}_{11}^{-} + \mathrm{H}_{2} \qquad \Delta H = 0.00 \text{ eV}, \\ &\mathrm{Si}_{n}\mathrm{H}_{2n+1}^{-} + \mathrm{SiH}_{4} = \mathrm{Si}_{n+1}\mathrm{H}_{2n+3}^{-} + \mathrm{H}_{2}. \end{split}$$

In order to activate these chemical reactions the silane molecules must be vibrationally excited

See Fridman et al, J. App. Phys. 79, 1303 (1996).

Typical structures of hydrogenated silicon nanoparticles formed starting from these chemical reactions

(a) Example of amorphous structure resulting from a growth mechanism in a pure silane plasma at room temperature in the absence of atomic hydrogen;



Q. Brulin, N. Ning, H Vach, J. Non-Cryst. Solids 352, 1055-1058 (2006)



# (b) Low atomic hydrogen flux giving rise to crystalline structures that are rich in hydrogen.

Q. Brulin, N. Ning, H Vach, J. Non-Cryst. Solids 352, 1055-1058 (2006)

(c) High atomic hydrogen flux yielding crystalline structures relatively poor in hydrogen that are similar to those predicted for pure silicon clusters;





 $Si_{29}H_{24}$  cluster under hydrogen bombardment

Q. Brulin, N. Ning, H Vach, J. Non-Cryst. Solids 352, 1055-1058 (2006)

# NANOPARTICLE DETECTION AND METROLOGY

#### LASER LIGHT SCATTERING



 $I_{\perp} = C \cdot \Delta V \cdot \Delta \Omega \cdot n_p \cdot \frac{16\pi^4}{\lambda^4} \cdot r_p^6 \cdot \left| \frac{m^2 - 1}{m^2 + 2} \right|^2 \cdot I_{\perp}^i$  $I_{\prime\prime\prime} = C \cdot \Delta V \cdot \Delta \Omega \cdot n_p \cdot \frac{16\pi^4}{\lambda^4} \cdot r_p^6 \cdot \left| \frac{m^2 - 1}{m^2 + 2} \right|^2 \cdot I_{\prime\prime\prime}^i \cdot \cos^2 \theta$ 

The scattered intensity allows the detection but contains also information about the size, concentration and refractive index.

#### Multi-angle laser light scattering.

Ch. Hollenstein et al, PSST3, (1994), 278.

#### NANOPARTICLE DETECTION LASER LIGHT SCATTERING



Time evolution of the scattered intensities for the two polarization directions.



Time evolution of the size, concentration and refractive index of the dust particles during their growth.

Ch. Hollenstein et al, PSST3, (1994), 278.



**Photon counting techniques** : *M. Shiratani and Y. Watanabe, The Revue of Laser Engineering 26, 449-452 (1998).* 

0.4

0.6

 $T_{\rm on}$  (s)

0.8

In this size range : Rayleigh scattering  $\propto r_p^6 / \lambda^4$ sophisticated techniques for signal recovery

# NANOPARTICLE DETECTION LASER INDUCED INCANDESCENCE

#### Mainly used for soot particles detection



 $I_{LII}$  is proportional to the dust particles volume fraction.

Decrease characteristic time depends on the dust particle size.

Température 4000 3000 2000 0.5 15 2 25 õ 1 3 x 10 x 10<sup>-12</sup> LII 4 2 00 0.5 1 1.5 2 2.5 3 x 10

Particule de suie

A. Boiarciuc et al Applied Physics B83, (2006), 413.

# NANOPARTICLE DETECTION LASER INDUCED EVAPORATION



Laser fluence (10<sup>8</sup> Wm<sup>-2</sup>)

The emitted signal from the heated dust particles is much intense than the scattered one.

W. W. Stoffels et al Appl. Phys Letter 74, (1993), 259

# NANOPARTICLE DETECTION LASER INDUCED PARTICLE EXPLOSIVE EVAPORATION (LIPEE).

- Method based on the particle explosive evaporation induced by laser irradiation (LIPEE)
- Detection of particles in the nanometer scale and evidence of the 3 different growth phases.
- This experiment was performed using an XeCl laser (308 nm) with an energy density of 400 MW/cm<sup>2</sup>.



(L. Boufendi et al, J. Appl. Phys. 76, 148, 1994).

# NANOPARTICLE DETECTION LASER INDUCED PARTICLE EXPLOSIVE EVAPORATION (LIPEE).



The LIPEE signal intensity is rather proportional to the dust particle size.

radius (nm)

For the detection of particles formed in an industrial reactor these methods cannot be used. We have to look for other diagnostic tools.



We have to use the plasma and discharges properties.











#### **Detection of multigeneration systems**



#### **MICROWAVE RESONANT CAVITY METHOD**

Basic relation used to calculate the electron density :

$$n_e = \frac{2m_e\varepsilon_0(2\pi f)^2\Delta f}{e^2 f_0}$$

*f*: resonance frequency with plasma  $f_0$ :resonance frequency without plasma  $\Delta f$ : *f*-*f*<sub>0</sub>



mode  $TM_{110}$  f=2.72GHz

For a pure Ar plasma (30sccm, 10W) :  $n_e = 1.2 \ 10^{16} \text{m}^{-3}$ 

**Correlation between the electron density and electrical parameters.** 



accumulation



-80

-100

-120 L

The first decrease of the electron density is due to the formation of negative clusters. The time constant of this process is much longer than in the silane case.

Ar-SiH<sub>4</sub> chemistry

0.4

Temps (s)

0.5

0.2

0.3

0.1

-1.4

0.8

**1**0.2 0.8

0.7

0.6



#### Ar-CH<sub>4</sub> chemistry

**Three different phases:** 

- Nucleation, growth and accumulation of nanometer sized "clusters (nanocrystallites?),
- 1st agglomeration phase of the nanoclusters;
- -2<sup>nd</sup> agglomeration phase.

All these phases are well identified from  $V_{DC}$ ,  $3^{rd}$ harmonic of the discharge current and from the time evolution of the electron density.





1- The gas temperature has no effect on the negative ion formation but strongly influences chemical reaction

$$Si_nH_{2n+1}^- + SiH_4^* \rightarrow Si_{n+1}H_{2(n+1)+1} + 2H$$

A. A. Fridman et al J. Appl. Phys. 79, 1303 (1996)

2- This can also be related to the temperature dependence of the Brownian diffusion coefficients when Tg increases.

U. Bhandarkar et al, J. Phys. D: Appl. Phys. 36, 1399 (2003)

The negative ions formation is not affected by the gas temperature.

#### What does it happen if we cool down the gas instead of heating?



The nanocristallites critical size is also affected by the gas temperature:

 $Tg = 100 \circ C$   $d_{nc} \approx 2 nm$ 

- $Tg = 25 \circ C$   $d_{nc} \approx 3 nm$
- $Tg = 0 \circ C$   $d_{nc} \approx 6 nm$

## DISCUSSION

The observed temperature effect on the dust particle formation can show that this phenomenon is close to the homogeneous nucleation and growth of nanocrystallites in a supersaturated medium (gas or liquide).

See for example:

- 1-J. B. Anderson et al, J. Atm. Sci., 33, 822, 1976.
- 2- S. Auer and D. Frenkel, Nature Vol. 409, 1020, 2001.
- 3- P. Peeters et al, J. Chem. Phys., 12, 5647, 2002.
- 4- J. W. P. Schmelzer, Mater. Phys. Mech., 6, 21, 2003.

In our experiments, we are operating at very low silane dilution in argon. However, the induction of nucleation seeds  $SiH_3^-$  could change the conditions.

### DISCUSSION

In this case the nucleation rate is given by  $J = J_0 \exp\left[-\frac{\Delta G}{k_B T}\right]$ 

 $\Delta G$  is the free energy variation during the phase transition or the required energy to form a nanocrystallite and the kinetics prefactor J<sub>0</sub> is related to

- the number of nucleation centers (seeds) which are for us the number of negative ions  $SiH_3^-$ , and

-the number of formed nanocristallites

#### **DISCUSSION**

The free energy variation  $\Delta G$  between the two phases can be expressed as follow:

$$\Delta G = -n_a \Delta \mu + \sigma A$$

with:

n<sub>a</sub> the number of atoms in the nanocristallites,

 $\Delta\mu$  is the difference of the chemical potentials per mole or particles in both phases,

 $\sigma$  is the surface tension on the nanocrystallites and

A their area.


The critical radius of the nanocrystallites corresponds to the maximum of  $\Delta G$  and is given by

$$r_c = \frac{2\sigma}{n_c \Delta \mu}$$

r<sub>c</sub> increases when T decreases.

Therefore if we decrease the gas temperature we can grow up bigger nanocrystallites.



# APPLICATIONS

NANOTECHNOLOGIES CAN BRING SOLUTIONS IN MANY DOMAINES SUCH AS:

- Energy production and storage
- Reduction of the size and energy consumption of nanoelectronique components
- Production and storage of Hydrogen
- Water cleaning
- Solution for the actual diseases (cancer etc...)
- Biomedical applications

- .....

#### NANOSTRUCTURED THIN LAYERS



#### WIDE RANGE OF APPLICATIONS

**Chemistry :** nanocatalysts synthesis, specific area  $100 \text{ m}^2/\text{g}$  for 100 nm size particles. **Mechanics** : super-hard coatings (ceramic or metallic particles or CNT' s included in amorphous or polymer matrixes).

**Photoluminescente devices** : the wavelength is size dependent.

**Optoelectronics**: silicon nanocrystallites based sensors for UV radiations detection for example.

**Solar cells** : Polymorphous silicon based cells (higher and stable efficiency vs a-Si:H **New lasers** : Silicon based lasers. Relatively important optical gain has been obtained in nanostructured  $SiO_2$ . A challenge for silicon

#### **POLYMORPHOUS SILICON THIN LAYERS**

#### **Strategy for film deposition :**

optimizing nanoparticles contribution and avoiding powder formation



#### Higher efficiency and stability compared to a-Si:H



#### SAED analysis. ns-Si:H; T<sub>on</sub>=5s, 100°C



Sample	ring	d <sub>hkl</sub>	hkl	a (Å)	Space group
ns-Si:H	1	2,11	111	3.659	FCC
	2	1,83	200	3.654	Fm3m (225)
	3	1,29	220	3.649	
	4	1,10	311	3.640	
	5	1,05	222	3.625	
	6	0,84	331	3.647	
	7	0,81	420	3.616	

FCC structure, a= 0.365 nm.

The arrows point out also Diamond like diffraction spots

#### **Micro-Raman analysis**



 $\Delta \omega$  is the Raman peak shift related to the crystallite size;

W is the peak width.

Sample	<b>P</b> <sub>LASER</sub>	Parameters		Size and volume fraction		
	$(kW/cm^2)$					
		$\Delta \omega$	W	$X_C$	$D_Z$	
		$(cm^{-1})$	$(cm^{-1})$	(%)	<i>(nm)</i>	
ns-Si:H	0.34	8.1	17.8	20.1	2.85	

#### **SINGLE-ELECTRON DEVICES**

**Requirements** : devices operating at room temperature.

-nanocrystallites (quantum dots) of 2-5 nm

-concentration of  $10^{11}$  to  $10^{12}$  cm<sup>-2</sup>



T. Baron et al, Applied Surface Science 164, 29-34 (2000)

- A. Dutta et al, Jpn. J. Appl. Phys. 39, 264-267 (2000).
- S. Oda, Tokyo Insitute of Technology, Japan

In general the crystallites are deposited using LPCVD. They have a dome like shape.



## **OTHER CHALLENGES**

# Size of "killer particles" is rapidly shrinking into the nano-regime

YEAR **1G G 16G G** Memory 256G Feature size, nm **D**<sub>killer particle</sub>, nm

> Source: National Technology Roadmap for Semiconductors Workshop, 2004 http://www.itrs.net

## **FUSION PLASMA CONTAMINATION**

Wall erosion Impurities in the plasma Radio-toxicity of dust particles

J. Winter, Phys. Plasmas 7, 3862 (2000)





## **TOKAMAKS CONTAMINATION**





- Difficulty
  - Powder formation;

- Flaking of the deposited layers on the walls during the plasma phases.



FIG. 2. Large flake of redeposited material from a TEXTOR limiter. The length of the white bar corresponds to 0.1 mm.

## **SAFETY AND HEALTH CARE ISSUES**

There is a lack of regulation codes in the area of nanoparticles manipulation and working conditions

Also due to their size nanoparticles can remain hours in levitation in air at atmospheric pressure.

They can also penetrate and accumulate deeply in human tissues.

This require the development of robust tools for the detection, metrology and chemical and morphological properties characterization of the nanoparticles.

#### **SAFETY AND HEALTH CARE ISSUES**



Talle
 Concentration
 Generation
 Generation

The particle size and concentration cannot be measured using light scattering due to the very small scattering cross section.

Development of method based on the analysis of the modification of the plasma and discharge properties induced by the presence of the nanoparticles.

#### Chemical composition can be analyzed using LIBS

$$\mathbf{r}_{D} = -\frac{\epsilon_{0}V_{s}\left(A_{B} + A_{M}\right)}{qV_{0}\chi} \times \frac{\Delta V_{DC}}{V_{DC}\Delta n_{e_{max}}}$$
$$r_{D}N_{D} = \frac{qV_{0}}{4\pi\epsilon_{0}V_{s}}\Delta n_{e_{max}}$$

## **SAFETY AND HEALTH CARE ISSUES**

#### **MORPHOLOGY ANALYSIS**

#### DUST PARTICLE MORPHOLOGY CHARACTERIZATION USING SAXS AND WAXS

10.0000



• 10.5mm • 15,5mm Scattered Intensity (cm<sup>-1</sup>) 1.0000 • 20mm 26mm • 31mm □ 34mm 0.1000 0.0100 0.0010 0.0001 0.10 0.01 1.00 a(nm<sup>-1</sup>)

From this kind of measurements we can deduce the size distribution functions and also the form and the surface properties of the dust particles. J. B. A. Mitchell et al J. Appl. Phys. 100, 124918 2006

Asbestos for example has no chemical reactivity but has fibber morphology.

## CONCLUSIONS

- Dusty or complex plasmas are a rather new research field in physics with new aspects. It is still in development.
- Step-wise dust particle formation mechanisms; new theoretical models for carbon and silicon chemistries.
- Many new applications have been developed, others are underway.
- Connection between different communities.
- Many challenges





d'une étoile géante





## **Thank you**

